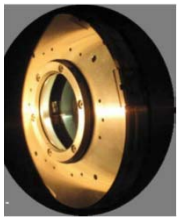
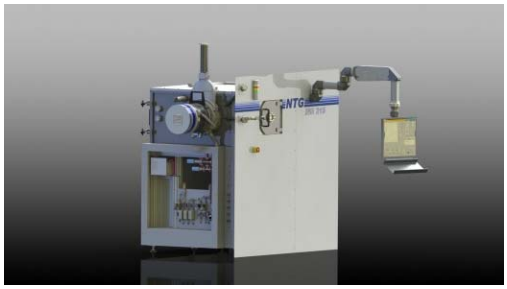
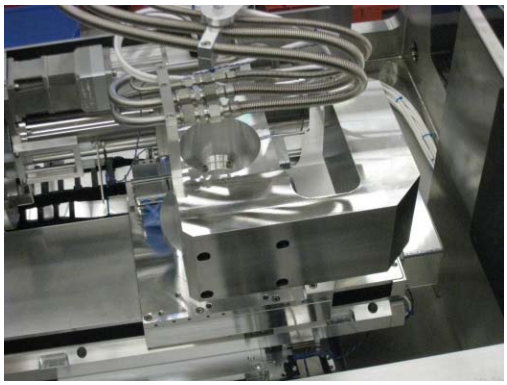
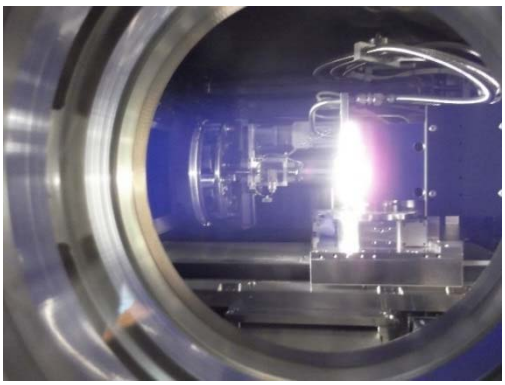


# (R)-IBE 215







**Technical data:**

| | |
|---|---|
| Working range: | Ø215mm, resp. 152.4 x 152.4mm<br>Ø8.5 inches, resp. 6 x 6 inches |
| Thickness: | 20mm (0.8 inches) |
| Weight: | max. 2kg (4.4 lb.) |
| Contact angle: | 0-90° |
| Rotation speed: | 0-10 rpm |
| Shape: | concave, convex, plane<br>spherical, aspherical, freeform |
| Load lock system: | yes, loading time < 2min. |

**Number of axes:**

| | |
|---|---|
| Type: 215 | X,Y,A,B |
| Travel | X > 500mm<br>Y = 300mm<br>A ± 95°<br>B = 360° |

**Dimensions:**

| | |
|---|---|
| Weight: | 2000kg (4400 lb.) |
| Dimensions:(wxhxd) | 2,8m x 2,4m x 1,4m<br>(110 x 94 x 55 inches) |
| Footprint: | 4m x 2m<br>157 x 79 inches |

**Power supply:**

| | |
|---|---|
| Mains requirement: volt. | 400V – 3 phases +N+PE |
| Mains requirem.: frequency | 50-60 Hz |
| Current per phase max.: | 32A |
| Power requirement: | max. 44 kW / Average 6,5kW |

**Utilities supply:**

| | |
|---|---|
| Nitrogen: | |
| Pressure Ion source: | 2 bar g (30 psi) |
| Pressure vac. Chamber: | 1..3 bar g (15..45 psi) |
| Purity: | 99,9990 % (5.0) |
| Argon&Oxygen: | |
| Pressure: | 2 bar g (30 psi) |
| Purity: | min. 99.9990%(5.0) |
| Compressed air: | |
| Pressure: | 4..10 bar g (60..150 psi) |
| Quality class to ISO 8573-1 | 2 4 1 |
| Cooling water: | |
| Pressure: | 3..4 bar g (45..60 psi) |
| Temp.: | > dew point, max. 25°C (77°F) |
| Vacuum pumps exhaust | pipe DN 40 |

The IBE-215 is a procedural plant for inert gas ion beam etching as well as for reactive ion beam etching. He-backside cooling, SIMS for end point detection, Interface for clean room, beam monitoring with Faraday cup array and other helpful features are available .



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